Particulate Contamination Analysis via Scanning Electron Microscopy

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Overview

- Review of Carbon extraction replicas
- TEM sample of 60121
- Replica Cleaning of acid etched 60125
- Replica Cleaning of SAP 50719
- Conclusions

Extraction Replicas

- a) "Dirty" Genesis sample
- b) Cellulose acetate replica film wetted with acetone applied to and removed from sample
- c) Replica coated with 60 nm of carbon
- d) Replica with cellulose acetate film removed by acetone vapor.



TEM Grid Containing Replica Film

Sample 60121 – Uncleaned Si



TEM Grid Containing Replica Film

Sample 60121 – Uncleaned Si



Qualitative EDX Analysis of Extracted Particles

Sample 60121 – Uncleaned Si







Analysis of Acid-etched Si 60125



Analysis of Acid-etched Si 60125

Submicron Contamination of 60125



Analysis of Acid-etched Si 60125



- 1 Silicon
- 2 Carbon

Paint Particle - Acid-etched Si 60125



Focused Ion Beam Fiducial Marks







Mag = 7.68 K X

EHT = 15.00 kV Signal A = InLens Date :18 Feb 2009 Pixel Size = 47.8 nm Time :10:39:22 WD = 5.7 mm



Mapped Area 6 of Acid-etched Si 60125 - Replica



Conclusions

- Cellulose acetate replicas are effective in removing particles from Genesis samples.
- SEM can be used to qualitatively measure the contribution of each type of particulate.
- Replica films can only remove some of the particles from acid-etched samples. It is hypothesized that the acid-etching may create a "glue" for some of the particles.

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Questions?